

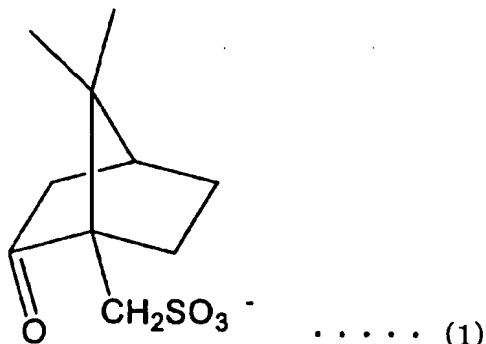
CLAIMS

1. A negative resist composition comprising at least an alkali-soluble resin, a cross-linking agent which is cross-linked with the alkali-soluble resin by the action of an acid, and an onium salt as a photoacid generator, in which the anion component of the onium salt is at least a sulfonate having a polycyclic structure.

10 2. The negative resist composition according to claim 1 further comprising an acidic compound and/or a basic compound.

3. The negative resist composition according to claim 1 or 2, wherein the polycyclic structure is at least one selected from a group consisting of adamantane, tricyclodecane, tetracyclodecane, isobornyl, norbornane, adamantane alcohol, norbornane lactone, and derivatives thereof.

15 4. The resist composition according to any one of claims 1 to 3, wherein the anion component of the onium salt is a sulfonate represented by the following general formula (1).



5. The negative resist composition according to any one of claims 1 to 4, wherein the cation component of the onium salt is an iodonium salt.

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6. A method for forming a resist pattern comprising the steps of: forming at least a photoresist layer on a substrate using the negative resist composition according to any one of claims 1 to 5, and forming the desired photoresist pattern by applying 10 exposure and development processes to the photoresist layer.